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# Uniform growth of MoS<sub>2</sub> films using ultra-low MoO<sub>3</sub> precursor in one-step heating chemical vapor deposition

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## Abstract

In chemical vapor deposition (CVD), homogeneous molybdenum vapor concentration is important in synthesizing uniform thickness and large coverage of two-dimensional molybdenum disulfide (2D-MoS<sub>2</sub>) films. Here, we synthesize few-layer MoS<sub>2</sub> films with uniform thickness and adequate coverage over 50 mm<sup>2</sup> size area using ultra-low molybdenum trioxide (MoO<sub>3</sub>) precursor placed directly under a face-down silicon dioxide/silicon (SiO<sub>2</sub>/Si) substrate in one-step heating CVD. The precursor mass is controlled by dispersing MoO<sub>3</sub> powder in ethanol (C<sub>2</sub>H<sub>5</sub>OH) and varying the volume of MoO<sub>3</sub>/C<sub>2</sub>H<sub>5</sub>OH solution coated on SiO<sub>2</sub>/Si substrates into 10, 20 and 25 μL. Field emission scanning electron microscopy images reveal that 20 μL MoO<sub>3</sub>/C<sub>2</sub>H<sub>5</sub>OH solution produces ~93% area coverage of 2D-MoS<sub>2</sub> films. The average Raman spectra show the typical presence of MoS<sub>2</sub> peaks around 378.8 cm<sup>-1</sup> and 404 cm<sup>-1</sup> referring to the E<sub>12g</sub> and A<sub>1g</sub> modes, respectively. The difference between the two Raman modes for all samples is ~25 cm<sup>-1</sup>, indicating few-layer MoS<sub>2</sub> films. The thickness of MoS<sub>2</sub> films is estimated at around 2.8 ± 0.44 nm and 3.2 ± 0.43 nm (~6 layers) using atomic force microscopy analysis. These findings suggest that ultra-low MoO<sub>3</sub> precursor is useful to produce uniform thickness and high coverage few-layer MoS<sub>2</sub> films using one-step heating CVD. © 2022 Elsevier B.V.

## Author keywords

Chemical vapor deposition ; Mo vapor concentration; Molybdenum disulfide; Molybdenum trioxide; One-step heating ; Uniform thickness

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